

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Christophe MALEVILLE et al. Confirmation No.
Application No: Group Art Unit:
Filing Date: Examiner:
For: METHOD FOR PRODUCING A HIGH Atty. Docket No.: 4717-11700
QUALITY USEFUL LAYER ON A SUBSTRATE

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Sir:

Pursuant to applicants' duty of disclosure under 37 C.F.R. 1.56, enclosed is a PTO form 1449 which lists (3) cited references for the Examiner's review and consideration.

Pursuant to the recent rule change in the Official Gazette, copies of the U.S. references are not submitted. It is respectfully requested that these references be made of record in this application by the Examiner's completion and return of the PTO Form 1449.

No fee or certification is believed to be due for this submission since the references are being submitted concurrent with the filing of this application. Should any fees be required, however, please charge such fees to **Winston & Strawn** Deposit Account No. 50-1814.

Date: _____

10/21/03

Respectfully submitted,



Allan A. Fanucci (Reg. No. 30,256)

WINSTON & STRAWN LLP
CUSTOMER NO. 28765
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Enclosures

LIST OF REFERENCES CITED BY APPLICANT <i>(Use several sheets if necessary)</i>					ATTY. DOCKET NO.:		APPLICATION SERIAL NO.:	
					4717-11700			
					APPLICANT:			
					Christophe MALEVILLE et al.			
					FILING DATE:		GROUP:	
U.S. PATENT DOCUMENTS								
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
	AA	6,362,076 B1	3/2002	Inazuki et al.	438	458		
	AB							
	AC							
	AD							
	AE							
	AF							
FOREIGN PATENT DOCUMENTS								
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	AG	FR797713 English Abstract	2/2001	France			X	
	AH							
	AI							
OTHER REFERENCES <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>								
	AJ	Aditya Agarwal, et al., "Efficient production of silicon-on-insulator films by co-implantation of He ⁺ with H ⁺ ", Applied Physics Letters, vol. 72 (1998), pages 1086-1088.						
	AK							
	AL							
	AM							
EXAMINER					DATE CONSIDERED			
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609 ; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								